## 1,2-Fluorine Atom Migration in the 1,1,2-Trifluoroethyl Radical

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The reactions of energetic tritium (T) with 1,1,2-trifluoroethylene suggest that the excited  $\cdot$ CF<sub>2</sub>CHTF radical formed by tritium addition undergoes 1,2-fluorine migration, and eventually gives CF<sub>2</sub>=CHT as the major product.

Chlorine and bromine have been found to undergo 1,2-migration readily in various chemical species,1—3 whereas 1,2-migration of fluorine is rare.4—6 Recently, Siefert *et al.* have investigated the reactions of recoil tritium with *cis-* and *trans-*difluoroethylenes, and found that the tritium-labelled parent molecules are formed mainly by the direct T-for-H substitution process, and that the CHTF-CHF radical formed by the recoil tritium addition process undergoes 1,2-fluorine

migration to give CF<sub>2</sub>=CHT as final decomposition product.<sup>7</sup> In the present work, reactions of energetic tritium atoms with 1,1,2-trifluoroethylene and with 1,1-difluoroethylene and vinyl fluoride for comparison have been studied.

Energetic tritium atoms were produced by the nuclear reaction <sup>3</sup>He(n,p)T. Sample mixtures containing the fluorinated ethylenes and <sup>3</sup>He were exposed to neutrons in an irradiation chamber of the TRIGA Mark II reactor of the

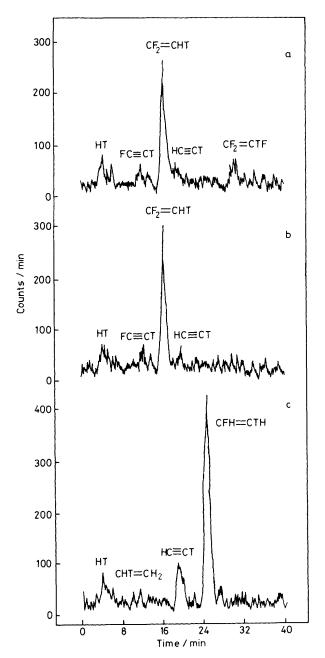


Figure 1. Radio-gas chromatograms of tritium-labelled products from the reactions of energetic tritium atoms with (a) CF<sub>2</sub>=CHF, (b) CF<sub>2</sub>=CH<sub>2</sub>, and (c) CFH=CH<sub>2</sub>.

Musashi Institute of Technology. The radioactive tritiumlabelled products in each irradiated sample were assayed using radio-gas chromatography.

The results, examples of which are in Figure 1, show the following. (i) In energetic tritium reactions with 1,1,2-trifluoroethylene (Figure 1a), tritium-labelled 1,1-difluoroethylene CF<sub>2</sub>=CHT was produced in unexpectedly high yield, whereas the tritium-labelled parent compound CF<sub>2</sub>=CTF was a minor product, as were TC=CF and TC=CH. (ii) In the cases of 1,1-difluoroethylene and vinyl fluoride (Figure 1b and c) the major products were the tritium-labelled parent compounds CF<sub>2</sub>=CHT and CFH=CHT, respectively; the minor products were TC=CF, TC=CH, and CHT=CH<sub>2</sub>. It is well known that thermal hydrogen atoms preferentially add to the less substituted carbon atom of fluorinated ethylenes.<sup>8</sup>

Therefore, tritium should also add to the less fluorinated carbon atom. In the case of 1,1,2-trifluoroethylene, most of the tritium atoms should add to the =CHF group; accordingly the excited radical 'CF2-CHTF is mainly formed. Since the C-F bond is stronger than the C-H and C-T bonds, the major tritium-labelled product formed from the radical by elimination should be CF<sub>2</sub>=CFT, and CF<sub>2</sub>=CHT should be a minor product. However, an unexpectedly large amount of CF<sub>2</sub>=CHT was obtained experimentally. This apparent contradiction may be explained by the following mechanism involving a 1,2-fluorine atom migration. The excited ·CF<sub>2</sub>-CHTF radical is converted into the alternative excited radical CF<sub>3</sub>-CHT by 1,2-fluorine migration, in which a fluorinebridged complex may be formed as an intermediate. The tritium-labelled 1,1-difluoroethylene may then be readily formed by the expulsion of a fluorine atom from the -CF<sub>3</sub> group of the excited CF<sub>3</sub>-CHT radical. In this system, it is difficult for the ·CF2-CHTF radical to form a hydrogenbridged complex to facilitate 1,2-hydrogen migration. If the radical were capable of this migration, the tritium-labelled parent compound CF<sub>2</sub>=CFT would be produced in high yield.

Scott and Jennings investigated the addition of thermal hydrogen atoms to trifluoroethylene.<sup>8</sup> They irradiated hydrogen containing a small amount of 1,1,2-trifluoroethylene with a drop of mercury with a low-pressure mercury lamp, and the products were analysed by gas chromatography and mass spectrometry. An unexpected product, CF<sub>3</sub>CH<sub>2</sub>CH<sub>2</sub>CF<sub>3</sub>, was obtained in high yield, but the mechanism for its formation was not discussed. We may now provide an explanation by the following mechanism, involving 1,2-fluorine migration. The excited CF<sub>2</sub>-CH<sub>2</sub>F radical, formed by the addition of hydrogen to CF<sub>2</sub>-CHF, is converted into the excited CF<sub>3</sub>-CH<sub>2</sub> radical by 1,2-fluorine migration. The unexpected C<sub>4</sub>-product CF<sub>3</sub>CH<sub>2</sub>CF<sub>3</sub> can be formed from the CF<sub>3</sub>-CH<sub>2</sub> radicals by an association process after collisional deactivation.

In the case of the 1,1-difluoroethylene system, the tritium atom adds almost exclusively to the = $CH_2$  group, and so the excited  $\cdot CF_2$ - $CH_2T$  radical is mainly formed. This radical is not capable of 1,2-fluorine migration, since both fluorine atoms are bound to a radical carbon. As a result, the tritium-labelled parent compound  $CF_2$ =CHT is formed on elimination of hydrogen from the radical. No cis- or trans-1,2-difluoroethylene was found, demonstrating that such a 1,2-fluorine migration does not easily occur in this system.

The activation energies of the 1,2-fluorine and 1,2-hydrogen migration reactions in 1,1,2-trifluoroethyl and 1,2-difluoroethyl radicals were estimated by INDO calculations. The results suggest that the excited •CF<sub>2</sub>-CHTF and •CFH-CFHT radicals are energetically capable of 1,2-fluorine, but not 1,2-hydrogen, migration.

We thank Professor N. Ishikawa of the Tokyo Institute of Technology for supplying the 1,1,2-trifluoroethylene, 1,1-difluoroethylene, and vinyl fluoride.

Received, 14th July 1986; Com. 973

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